

Photo Mask Series

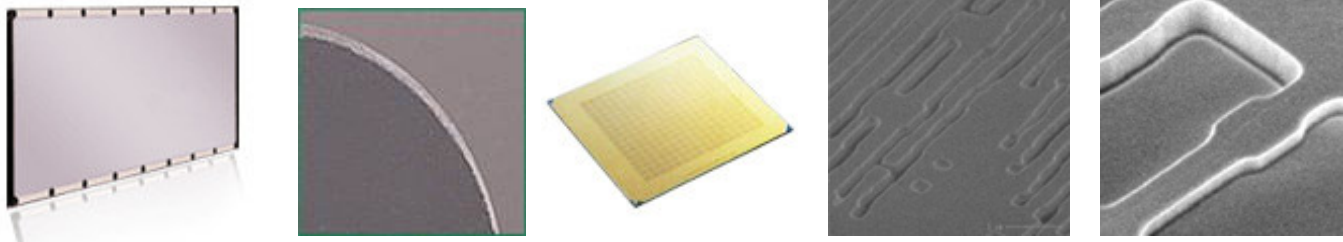


Key Features:

- *High Quality* , with Minimum Feature Size of 0.1 μm
- Zero Defect
- *Economical Price*, Due to Low Fabrication Cost & High Production Capacity
- All Design Formats Acceptable
- Quick Response, within 12 Hours

Main Applications:

Masks are integral components in the lithographic process of semiconductor manufacturing. They contain transparent substrate which covered patterned opaque layer on it. This architecture used in lithography to block resist exposure in selected area and transfer circuit patterns from mask to wafer for mass production.



Ordering Information:

Material: Soda-lime glass (SL), Synthetic quartz (QZ)
Minimum Feature Size: 1 μm (1), 2 μm (2), 4 μm (4), 8 μm (8), 10 μm (10), or per your request
Plate Size: 25mm x 25mm (025-025), 50mm x 50mm (050-050), 75mm x 75mm (075-075), 100mm x 100mm (100-100), 125mm x 125mm (125-125), 150mm x 150mm (150-150), 175mm x 175mm (175-175), 200mm x 200mm (200-200), or per your request
Plate Thickness: 1.5mm (1.5), 2mm (2), 2.5mm (2.5), 3mm (3), 3.5mm (3.5), 4mm (4), 4.5mm (4.5), 5mm (5), or per your request

Part Number Definition: PMS-①/②/③-④

- ①-Material
- ②-Minimum Feature Size
- ③-Plate Size
- ④-Plate Thickness

Sample: "PMS-QZ/2/075-075-2" means "Photo Mask Series, Material is Synthetic Quartz, Minimum Feature Size is 2 μm , Plate Size is 75mm x 75mm, Plate Thickness is 2mm".

The items listed above are ordinal mask standards. We can manufacture special mask standard. Please provide your design to us and our engineers will analyse for you.

Contact Information:

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